

<b>Notice of References Cited</b>	Application/Control No. 10/586,369		Applicant(s)/Patent Under Reexamination BOHMHAMMEL ET AL.	
	Examiner Ngoc-Yen M. Nguyen		Art Unit 1793	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2008/0072818	03-2008	Mostarshed et al.	117/087
*	B	US-5,910,295	06-1999	DeLuca, John P.	423/337
*	C	US-5,716,590	02-1998	Roewer et al.	423/342
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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	N					
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Valente, Gianluca et al, "Reduced order model for the CVD of epitaxial silicon from silane and chlorosilanes", Journal of Crystal Growth 230 (2001), pp. 247-257.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.